

PHOTOMASK FABRICATION METHOD, PHOTOMASK, AND EXPOSURE METHOD THEREOF

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Application No. 09/982,305

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Replacement Drawings



FIG. 1

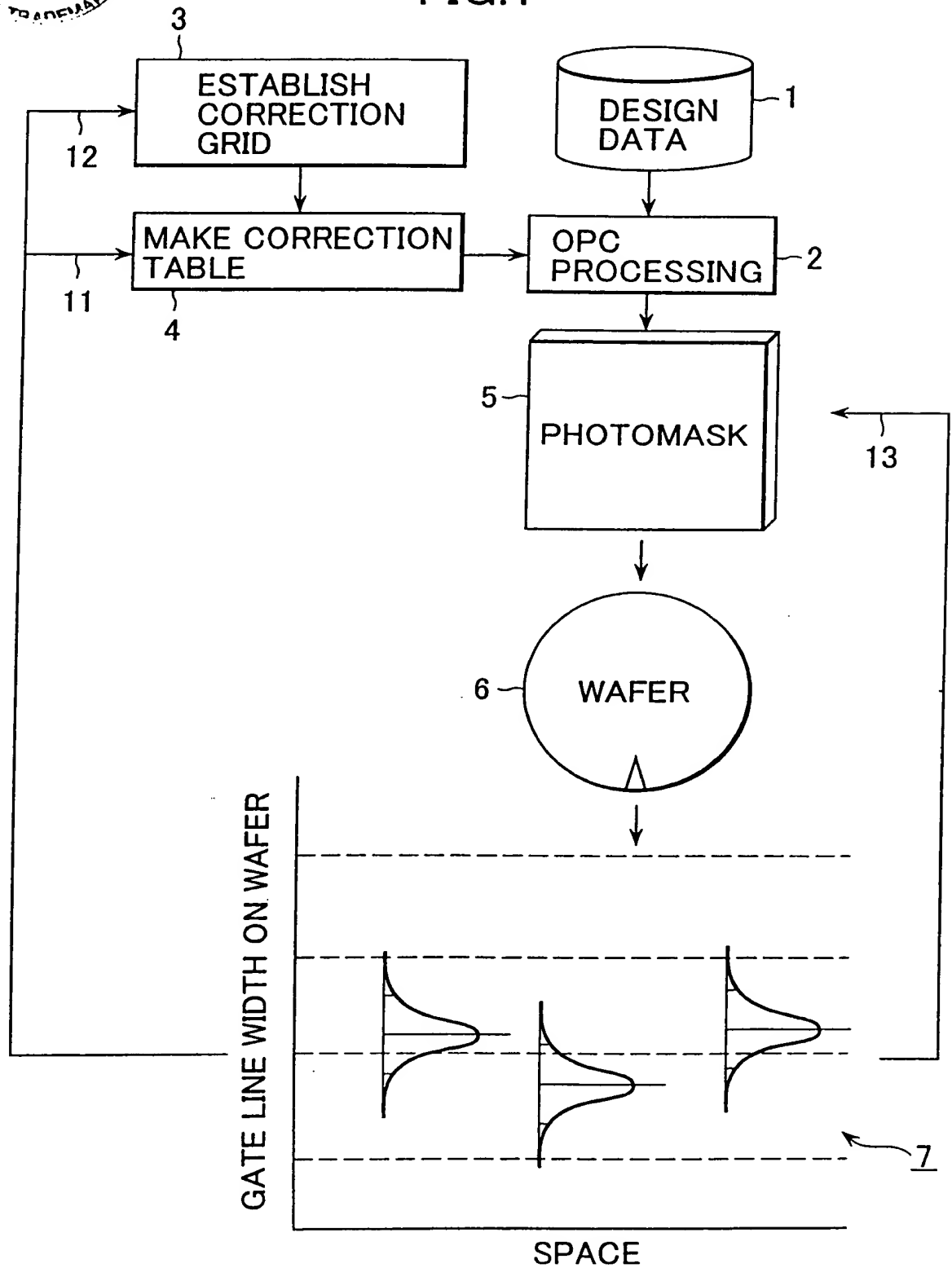


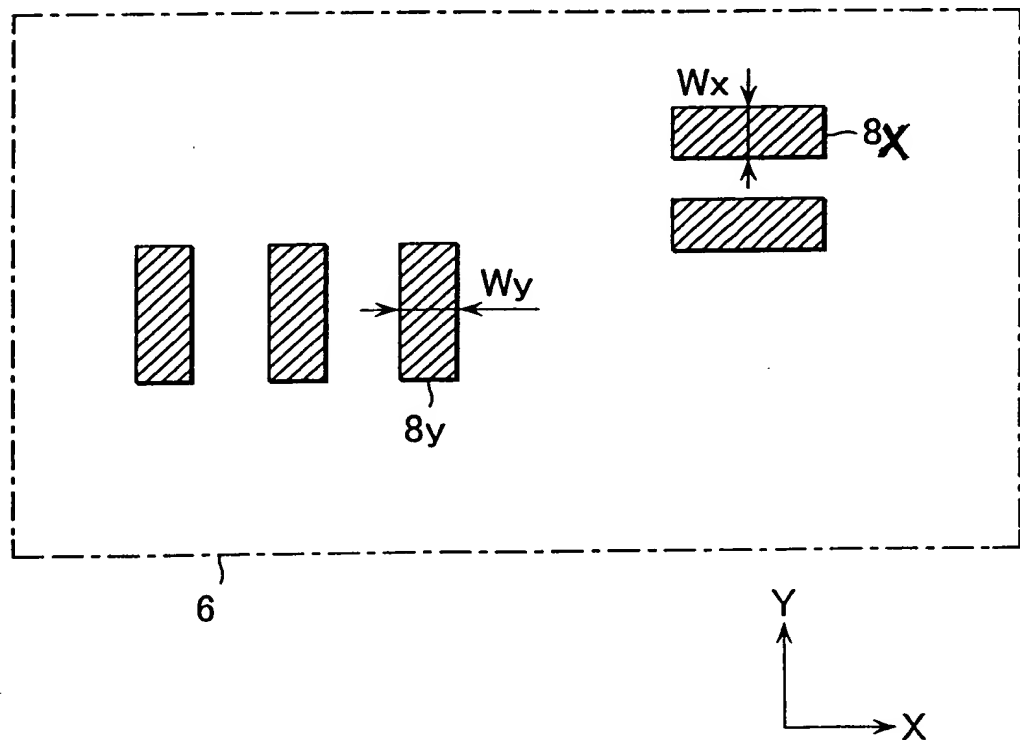


FIG.4

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		SPACE					
GATE LINE WIDTH	( $\mu\text{m}$ ) \n ( $\mu\text{m}$ )	0.25 $\mu$	0.3 $\mu$	0.35 $\mu$	0.4 $\mu$	0.5 $\mu$	0.55 $\mu$
	0.2 $\mu$	2.5	5	7.5	10	12.5	15

FIG.5





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FIG.13A

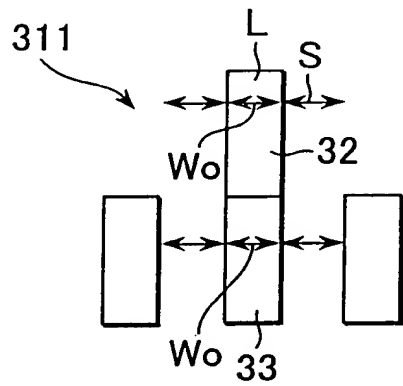
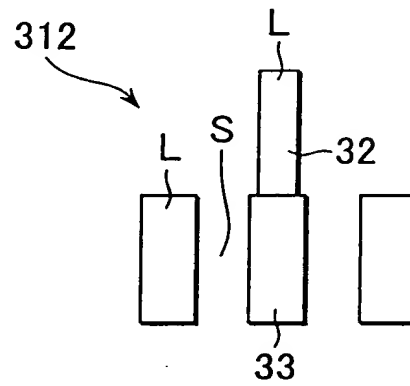
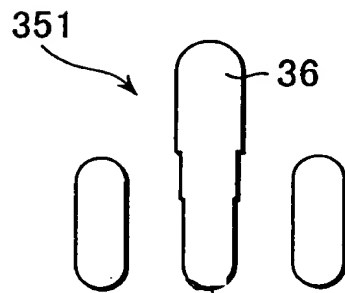


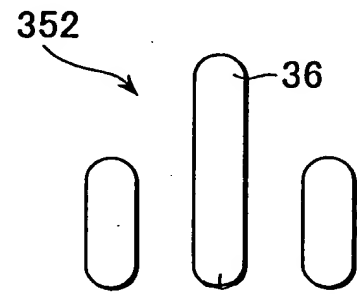
FIG.13B



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PRECORRECTION



POSTCORRECTION